L Number	Hits	Search Text	DB	Time stamp
1	4634	(134/2,4,21,22.1,22.12).CCLS.	USPAT;	2004/06/18 19:14
		·	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
	0.5	//424/2 4 24 22 4 22 42) CCI C) and //first with /film or	IBM_TDB USPAT;	2004/06/18 19:55
2	85	((134/2,4,21,22.1,22.12).CCLS.) and ((first with (film or coating or layer)) or ((silicon adj oxide) or SiO)) and	US-PGPUB;	2004/00/10 15.55
		((second with (film or coating or layer)) or ((silicon adj	EPO; JPO;	
		nitride) or SiN)) and ((clean\$3 or etch\$3) and ((hydrogen	DERWENT;	
		adj fluoride) or HF) and (tube or wall or exhaust or bell or	IBM_TDB	
ļ		chamber))	_	
3	57	(((134/2,4,21,22.1,22.12).CCLS.) and ((first with (film or	USPAT;	2004/06/18 19:40
		coating or layer)) or ((silicon adj oxide) or SiO)) and	US-PGPUB;	
		((second with (film or coating or layer)) or ((silicon adj	EPO; JPO;	
		nitride) or SiN)) and ((clean\$3 or etch\$3) and ((hydrogen	DERWENT;	
		adj fluoride) or HF) and (tube or wall or exhaust or bell or	IBM_TDB	
_	200	chamber))) and (@ad<=19991124 or @rlad<=19991124)	LICDAT	2004/06/19 20:00
4	3054	((134/2,4,21,22.1,22.12).CCLS.) and (@ad<=19991124 or	USPAT; US-PGPUB;	2004/06/18 20:09
		@rlad<=19991124)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
5	2	((((134/2,4,21,22.1,22.12).CCLS.) and (@ad<=19991124 or	USPAT;	2004/06/18 19:56
	_	@rlad<=19991124)) and ((exhaust adj pipe) same open	US-PGPUB;	
		same close)	EPO; JPO;	
		-	DERWENT;	
[IBM_TDB	
6	540	(134/22.11).CCLS.	USPAT;	2004/06/18 19:55
			US-PGPUB;	
			EPO; JPO; DERWENT;	
			IBM_TDB	
8	0	((134/22.11).CCLS.) and ((exhaust adj pipe) same open	USPAT;	2004/06/18 20:08
	U	same close)	US-PGPUB;	200 1/00/10 20:00
		Sume close)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
7	4.	((134/22.11).CCLS.) and ((first with (film or coating or	USPAT;	2004/06/18 20:08
		layer)) or ((silicon adj oxide) or SiO)) and ((second with	US-PGPUB;	
		(film or coating or layer)) or ((silicon adj nitride) or SiN))	EPO; JPO;	
		and ((clean\$3 or etch\$3) and ((hydrogen adj fluoride) or	DERWENT;	
	F066	HF) and (tube or wall or exhaust or bell or chamber))	IBM_TDB USPAT;	2004/06/18 20:04
9 .	5066	(134/3,22.18,37,42).CCLS.	US-PGPUB;	2004/00/18 20:04
4			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
10	79	((134/3,22.18,37,42).CCLS.) and ((first with (film or coating	USPAT;	2004/06/18 20:08
		or layer)) or ((silicon adj oxide) or SiO)) and ((second with	US-PGPUB;	
		(film or coating or layer)) or ((silicon adj nitride) or SiN))	EPO; JPO;	
		and ((clean\$3 or etch\$3) and ((hydrogen adj fluoride) or	DERWENT;	
		HF) and (tube or wall or exhaust or bell or chamber))	IBM_TDB	2004/06/42 22 22
11	1	((134/3,22.18,37,42).CCLS.) and ((exhaust adj pipe) same	USPAT;	2004/06/18 20:09
		open same close)		
.				
	_	open same close)	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	

			T=	
12	52	(((((134/3,22.18,37,42).CCLS.) and ((first with (film or coating or layer)) or ((silicon adj oxide) or SiO)) and	USPAT; US-PGPUB;	2004/06/18 20:10
		((second with (film or coating or layer)) or ((silicon adj	EPO; JPO;	
		nitride) or SiN)) and ((clean\$3 or etch\$3) and ((hydrogen	DERWENT;	
		adj fluoride) or HF) and (tube or wall or exhaust or bell or	IBM_TDB	
		chamber))) (((134/3,22.18,37,42).CCLS.) and ((exhaust adj		
į		pipe) same open same close))) and (@ad<=19991124 or @rlad<=19991124)		
_	2	6383300.pn.	USPAT;	2004/02/20 14:52
	_	σοσοσοιμικ	US-PGPUB;	200 1/02/20 14.52
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	17	("4699805" "5015503" "5250092" "5328360"	USPAT	2004/02/20 15:47
		"5433784" "5554226" "5578132" "5637153"		·
		"5777300" "5851293" "5880032" "5914000"		
		"6099649" "6139642" "6159298" "6206971" "6238514").PN.		
_	17961	((118/715,724,725) or (156/345.29) or (134/1,1.3) or	USPAT;	2004/02/20 16:17
	17901	(116/715,724,725) of (136/545.29) of (134/1,1.5) of (216/37,58,63) or (438/694,699,703,706)).CCLS.	US-PGPUB;	2004/02/20 16:17
		(210/37/30/03) of (130/03/4/033/700/).ccc3.	EPO; JPO;	
٠			DERWENT;	
			IBM_TDB	
-	550	(((118/715,724,725) or (156/345.29) or (134/1,1.3) or	USPAT;	2004/02/20 17:29
		(216/37,58,63) or (438/694,699,703,706)).CCLS.) and	US-PGPUB;	
		((first with (film or coating or layer)) or ((silicon adj oxide)	EPO; JPO;	
		or SiO)) and ((second with (film or coating or layer)) or	DERWENT;	
		((silicon adj nitride) or SiN)) and ((clean\$3 or etch\$3) same	IBM_TDB	
_	419	((hydrogen adj fluoride) or HF)) ((((118/715,724,725) or (156/345.29) or (134/1,1.3) or	LICDAT	2004/06/19 16:21
_	413	((((116/713,724,723) of (136/343.29) of (134/1,1.3) of (216/37,58,63) or (438/694,699,703,706)).CCLS.) and	USPAT; US-PGPUB;	2004/06/18 16:31
		((first with (film or coating or layer)) or ((silicon adj oxide)	EPO; JPO;	
		or SiO)) and ((second with (film or coating or layer)) or	DERWENT;	
		((silicon adj nitride) or SiN)) and ((clean\$3 or etch\$3) same	IBM_TDB	
]	((hydrogen adj fluoride) or HF))) and (@ad<=19991124 or		
		@rlad<=19991124)		
-	384	(((((118/715,724,725) or (156/345.29) or (134/1,1.3) or	USPAT;	2004/02/20 17:33
		(216/37,58,63) or (438/694,699,703,706)).CCLS.) and	US-PGPUB;	
		((first with (film or coating or layer)) or ((silicon adj oxide)	EPO; JPO;	
		or SiO)) and ((second with (film or coating or layer)) or ((silicon adj nitride) or SiN)) and ((clean\$3 or etch\$3) same	DERWENT; IBM_TDB	
		((hydrogen adj fluoride) or HF))) and (@ad<=19991124 or	101-1_100	
		@rlad<=19991124)) not (((hydrogen adj fluoride) or HF)		·
		with dip)		
-	5	("5545291" "5904545" "5958794" "6468638"	USPAT	2004/02/20 16:42
		"6479395").PN.		
-	163	(((((118/715,724,725) or (156/345.29) or (134/1,1.3) or	USPAT;	2004/06/18 16:32
		(216/37,58,63) or (438/694,699,703,706)).CCLS.) and	US-PGPUB;	
		((first with (film or coating or layer)) or ((silicon adj oxide)	EPO; JPO;	
		or SiO)) and ((second with (film or coating or layer)) or ((silicon adj nitride) or SiN)) and ((clean\$3 or etch\$3) same	DERWENT; IBM_TDB	
		((hydrogen adj fluoride) or HF))) and (@ad<=19991124 or	ם עויים דייום ד	
		@rlad<=19991124)) not (((hydrogen adj fluoride) or HF)		
		with (dip or solution or wet))		
-	991	((first with (film or coating or layer)) or ((silicon adj oxide)	USPAT;	2004/06/18 19:17
		or SiO)) and ((second with (film or coating or layer)) or	US-PGPUB;	
		((silicon adj nitride) or SiN)) and ((clean\$3 or etch\$3) same	EPO; JPO;	
		((hydrogen adj fluoride) or HF) same (tube or wall or	DERWENT;	
]	exhaust or bell))	IBM_TDB	

			1	
-	749	(((first with (film or coating or layer)) or ((silicon adj oxide)	USPAT;	2004/06/18 16:32
		or SiO)) and ((second with (film or coating or layer)) or	US-PGPUB;	
1		((silicon adj nitride) or SiN)) and ((clean\$3 or etch\$3) same	EPO; JPO;	
1		((hydrogen adj fluoride) or HF) same (tube or wall or	DERWENT;	
1		exhaust or bell))) and (@ad<=19991124 or	IBM_TDB	
	_	@rlad<=19991124)		
-	319	((((first with (film or coating or layer)) or ((silicon adj oxide)	USPAT;	2004/02/20 18:02
!		or SiO)) and ((second with (film or coating or layer)) or	US-PGPUB;	
		((silicon adj nitride) or SiN)) and ((clean\$3 or etch\$3) same	EPO; JPO;	
		((hydrogen adj fluoride) or HF) same (tube or wall or	DERWENT;	
		exhaust or bell))) and (@ad<=19991124 or	IBM_TDB	
		@rlad<=19991124)) not (((hydrogen adj fluoride) or HF)		
!		with (dip or solution or wet))		
-	284	(((((first with (film or coating or layer)) or ((silicon adj	USPAT;	2004/02/20 17:34
	1	oxide) or SiO)) and ((second with (film or coating or layer))	US-PGPUB;	
		or ((silicon adj nitride) or SiN)) and ((clean\$3 or etch\$3)	EPO; JPO;	
]		same ((hydrogen adj fluoride) or HF) same (tube or wall or	DERWENT;	
		exhaust or bell))) and (@ad<=19991124 or	IBM_TDB	
		@rlad<=19991124)) not (((hydrogen adj fluoride) or HF)		
		with (dip or solution or wet))) not ((((((118/715,724,725) or		
		(156/345.29) or (134/1,1.3) or (216/37,58,63) or		
		(438/694,699,703,706)).CCLS.) and ((first with (film or		
		coating or layer)) or ((silicon adj oxide) or SiO)) and		
		((second with (film or coating or layer)) or ((silicon adj		
	ļ	nitride) or SiN)) and ((clean\$3 or etch\$3) same ((hydrogen		
		adj fluoride) or HF))) and (@ad<=19991124 or		
		@rlad<=19991124)) not (((hydrogen adj fluoride) or HF)		
Į l		with (dip or solution or wet)))		
-	2215	((first with (film or coating or layer)) or ((silicon adj oxide)	USPAT;	2004/02/20 18:01
		or SiO)) and ((second with (film or coating or layer)) or	US-PGPUB;	
ļ :		((silicon adj nitride) or SiN)) and ((clean\$3) same (tube or	EPO; JPO;	
		chamber or wall or exhaust or bell)) and ((hydrogen adj	DERWENT;	
		fluoride) or HF)	IBM_TDB	
-	676	(((first with (film or coating or layer)) or ((silicon adj oxide)	USPAT;	2004/06/18 16:32
		or SiO)) and ((second with (film or coating or layer)) or	US-PGPUB;	
		((silicon adj nitride) or SiN)) and ((clean\$3) near5 (tube or	EPO; JPO;	
		chamber or wall or exhaust or bell)) and ((hydrogen adj	DERWENT;	
		fluoride) or HF)) and (@ad<=19991124 or	IBM_TDB	
		@rlad<=19991124)		
-	462	((((first with (film or coating or layer)) or ((silicon adj oxide)	USPAT;	2004/02/20 18:03
		or SiO)) and ((second with (film or coating or layer)) or	US-PGPUB;	
		((silicon adj nitride) or SiN)) and ((clean\$3) near5 (tube or	EPO; JPO;	
		chamber or wall or exhaust or bell)) and ((hydrogen adj	DERWENT;	
		fluoride) or HF)) and (@ad<=19991124 or	IBM_TDB	
		@rlad<=19991124)) not (((hydrogen adj fluoride) or HF)		
		with (dip or solution or wet))		
-	980	((first with (film or coating or layer)) or ((silicon adj oxide)	USPAT;	2004/02/20 18:06
		or SiO)) and ((second with (film or coating or layer)) or	US-PGPUB;	
		((silicon adj nitride) or SiN)) and ((clean\$3) near5 (tube or	EPO; JPO;	
		chamber or wall or exhaust or bell)) and ((hydrogen adj	DERWENT;	
		fluoride) or HF)	IBM_TDB	

-	293	(((((((first with (film or coating or layer)) or ((silicon adj oxide) or SiO)) and ((second with (film or coating or layer)) or ((silicon adj nitride) or SiN)) and ((clean\$3) near5 (tube or chamber or wall or exhaust or bell)) and ((hydrogen adj fluoride) or HF)) and (@ad<=19991124 or @rlad<=19991124)) not (((hydrogen adj fluoride) or HF) with (dip or solution or wet))) not (((((((118/715,724,725) or (156/345.29) or (134/1,1.3) or (216/37,58,63) or (438/694,699,703,706)).CCLS.) and ((first with (film or coating or layer)) or ((silicon adj oxide) or SiO)) and ((second with (film or coating or layer)) or ((silicon adj nitride) or SiN)) and ((clean\$3 or etch\$3) same ((hydrogen adj fluoride) or HF))) and (@ad<=19991124 or @rlad<=19991124)) not (((hydrogen adj fluoride) or HF) with (dip or solution or wet))) or ((((first with (film or coating or layer)) or ((silicon adj oxide) or SiO)) and ((second with (film or coating or layer)) or ((silicon adj nitride) or SiN)) and ((clean\$3 or etch\$3) same ((hydrogen adj fluoride) or HF) same (tube or wall or exhaust or bell))) and (@ad<=19991124 or @rlad<=19991124)) not (((hydrogen adj fluoride) or HF) with (dip or solution or wet))) not (((((118/715,724,725) or (156/345.29) or (134/1,1.3) or (216/37,58,63) or (438/694,699,703,706)).CCLS.) and ((first with (film or coating or layer)) or ((silicon adj oxide) or SiO)) and ((second with (film or coating or layer)) or ((silicon adj nitride) or SiN)) and ((clean\$3 or etch\$3) same ((hydrogen adj fluoride) or HF))) and (@ad<=19991124 or @rlad<=19991124 or @rlad<=1999	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2004/02/20 18:10
-	25	(exhaust same (fluctuat\$3 with pressure)) and 118.clas.	DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/02/23 16:34
-	17	("4699805" "5015503" "5250092" "5328360" "5433784" "5554226" "5578132" "5637153" "5777300" "5851293" "5880032" "5914000" "6099649" "6139642" "6159298" "6206971" "6238514").PN.	IBM_TDB USPAT	2004/02/23 16:09
-	26	control\$3 same pressure same (exhaust adj pipe) same fluctuat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/06/18 16:33
-	80	pressure same (exhaust adj pipe) same fluctuat\$3	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/06/18 16:34
-	54	(pressure same (exhaust adj pipe) same fluctuat\$3) not (control\$3 same pressure same (exhaust adj pipe) same fluctuat\$3)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/23 17:13

_	2749	purge same repeat\$3	USPAT;	2004/02/23 17:16
	2713	parge same repeates	US-PGPUB;	2001,02,2017.10
	,		EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	10	(purge same repeat\$3) same (exhaust adj pipe)	USPAT;	2004/06/18 16:35
			US-PGPUB;	
			EPO; JPO;	· ·
1			DERWENT;	
			IBM_TDB	
-	424	((((118/715,724,725) or (156/345.29) or (134/1,1.3) or	USPAT;	2004/06/18 16:38
		(216/37,58,63) or (438/694,699,703,706)).CCLS.) and	US-PGPUB;	
		((first with (film or coating or layer)) or ((silicon adj oxide)	EPO; JPO;	
		or SiO)) and ((second with (film or coating or layer)) or	DERWENT;	
		((silicon adj nitride) or SiN)) and ((clean\$3 or etch\$3) same	IBM_TDB	
		((hydrogen adj fluoride) or HF))) and (@ad<=19991124 or		
	1	@rlad<=19991124)	LICDAT	2004/06/40 46 55
-	165	((((((118/715,724,725) or (156/345.29) or (134/1,1.3) or	USPAT;	2004/06/18 16:32
		(216/37,58,63) or (438/694,699,703,706)).CCLS.) and	US-PGPUB;	
		((first with (film or coating or layer)) or ((silicon adj oxide)	EPO; JPO; DERWENT;	
		or SiO)) and ((second with (film or coating or layer)) or	IBM TDB	
		((silicon adj nitride) or SiN)) and ((clean\$3 or etch\$3) same ((hydrogen adj fluoride) or HF))) and (@ad<=19991124 or	ם מו "ואופד	
		((hydrogen adj fluoride) or HF)) and (@ad<=19991124 or @rlad<=19991124)) not (((hydrogen adj fluoride) or HF)		
		with (dip or solution or wet))		
_	754	(((first with (film or coating or layer)) or ((silicon adj oxide)	USPAT;	2004/06/18 16:32
	,,,,	or SiO)) and ((second with (film or coating or layer)) or	US-PGPUB;	200 1, 00, 10 10.02
		((silicon adj nitride) or SiN)) and ((clean\$3 or etch\$3) same	EPO; JPO;	
		((hydrogen adj fluoride) or HF) same (tube or wall or	DERWENT;	
		exhaust or bell))) and (@ad<=19991124 or	IBM_TDB	
		@rlad<=19991124)		
-	695	(((first with (film or coating or layer)) or ((silicon adj oxide)	USPAT;	2004/06/18 16:33
		or SiO)) and ((second with (film or coating or layer)) or	US-PGPUB;	
		((silicon adj nitride) or SiN)) and ((clean\$3) near5 (tube or	EPO; JPO;	
		chamber or wall or exhaust or bell)) and ((hydrogen adj	DERWENT;	
		fluoride) or HF)) and (@ad<=19991124 or	IBM_TDB	
		@rlad<=19991124)		
-	1014	exhaust same (fluctuat\$3 with pressure)	USPAT;	2004/06/18 16:33
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
	27	control¢? came proceure came (exhaust adi pina) came	IBM_TDB	2004/06/18 16:33
_	2/	control\$3 same pressure same (exhaust adj pipe) same fluctuat\$3	USPAT; US-PGPUB;	2004/00/10 10:33
		Huctuaty3	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
<u> </u>	84	pressure same (exhaust adj pipe) same fluctuat\$3	USPAT;	2004/06/18 16:34
		Freezen - same (samuate any kiko) same madada	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB '	

	43	(((((((118/715,724,725) or (156/345.29) or (134/1,1.3) or (216/37,58,63) or (438/694,699,703,706)).CCLS.) and ((first with (film or coating or layer)) or ((silicon adj oxide) or SiO)) and ((second with (film or coating or layer)) or ((silicon adj nitride) or SiN)) and ((clean\$3 or etch\$3) same ((hydrogen adj fluoride) or HF))) and (@ad<=19991124 or @rlad<=19991124)) (((((118/715,724,725) or (156/345.29) or (134/1,1.3) or (216/37,58,63) or (438/694,699,703,706)).CCLS.) and ((first with (film or coating or layer)) or ((silicon adj oxide) or SiO)) and ((second with (film or coating or layer)) or ((silicon adj nitride) or SiN)) and ((clean\$3 or etch\$3) same ((hydrogen adj fluoride) or HF))) and (@ad<=19991124 or @rlad<=19991124)) not (((hydrogen adj fluoride) or HF) with (dip or solution or wet))) ((((first with (film or coating or layer)) or ((silicon adj oxide) or SiO)) and ((second with (film or coating or layer)) or ((silicon adj oxide) or SiN)) and ((clean\$3 or etch\$3) same ((hydrogen adj fluoride) or HF) same (tube or wall or exhaust or bell))) and ((@ad<=19991124) or @rlad<=19991124))) (((((first with (film or coating or layer))) or ((silicon adj oxide) or SiO)) and ((second with (film or coating or layer))) or ((silicon adj oxide) or SiO)) and ((second with (film or coating or layer)) or ((silicon adj intride) or SiN)) and ((clean\$3) near5 (tube or chamber or wall or exhaust or bell)) and ((hydrogen adj fluoride) or HF)) and (@ad<=19991124 or @rlad<=19991124)) ((whosen adj fluoride) or HF)) and (@ad<=19991124) or @rlad<=19991124)) (exhaust same (fluctuat\$3 with pressure)) (control\$3 same pressure same (exhaust adj pipe) same fluctuat\$3)) and @pd>=20040203 ((((((118775,724,725) or (156/345.29) or (134/1,1.3) or (216/37,58,63) or (438/694,699,703,706)).CCLS.) and ((first with (film or coating or layer)) or ((silicon adj intride) or SiN)) and ((clean\$3 or etch\$3) same ((hydrogen adj fluoride) or HF) with (dip or solution or wet)) ((((first with (film or coating or layer)) or ((silicon adj intride) or SiN)) and	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/06/18 17:47
		same (exhaust adj pipe) same fluctuat\$3) (pressure same (exhaust adj pipe) same fluctuat\$3)) and @pd>=20040203) and (@ad<=19991124 or		
-	10	@rlad<=19991124) (purge same repeat\$3) same (exhaust adj pipe)	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/06/18 17:04
Coardh Histo	F/19/04	 8:27:08 PM Page 6	IBM_TDB	<u></u>

-	1220	(exhaust adj pipe) same open same close	USPAT;	2004/06/18 19:41
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	777	((exhaust adj pipe) same open same close) and (reactor or	USPAT;	2004/06/18 17:13
		chamber or tube)	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
_	506	(((exhaust adj pipe) same open same close) and (reactor or	IBM_TDB USPAT;	2004/06/18 17:43
•] 500	chamber or tube)) and (etch\$3 or coat\$3 or deposit\$3 or	US-PGPUB;	2004/00/10 17.43
		clean\$3 or remov\$3)	EPO; JPO;	
		cicanips of removps)	DERWENT;	
			IBM_TDB	
_	496	((((exhaust adj pipe) same open same close) and (reactor or	USPAT;	2004/06/18 17:45
		chamber or tube)) and (etch\$3 or coat\$3 or deposit\$3 or	US-PGPUB;	, ,
		clean\$3 or remov\$3)) not (((((118/715,724,725) or	EPO; JPO;	
	,	(156/345.29) or (134/1,1.3) or (216/37,58,63) or	DERWENT;	
		(438/694,699,703,706)).CCLS.) and ((first with (film or	IBM_TDB	
		coating or layer)) or ((silicon adj oxide) or SiO)) and		
		((second with (film or coating or layer)) or ((silicon adj		
		nitride) or SiN)) and ((clean\$3 or etch\$3) same ((hydrogen		
		adj fluoride) or HF))) and (@ad<=19991124 or		
		@rlad<=19991124)) (((((118/715,724,725) or		
		(156/345.29) or (134/1,1.3) or (216/37,58,63) or (438/694,699,703,706)).CCLS.) and ((first with (film or		,
		coating or layer)) or ((silicon adj oxide) or SiO)) and		
		((second with (film or coating or layer)) or ((silicon adj		
		nitride) or SiN)) and ((clean\$3 or etch\$3) same ((hydrogen		•
		adj fluoride) or HF))) and (@ad<=19991124 or		
		@rlad<=19991124)) not (((hydrogen adj fluoride) or HF)		
		with (dip or solution or wet))) ((((first with (film or coating		
		or layer)) or ((silicon adj oxide) or SiO)) and ((second with		
		(film or coating or layer)) or ((silicon adj nitride) or SiN))		
		and ((clean\$3 or etch\$3) same ((hydrogen adj fluoride) or		
		HF) same (tube or wall or exhaust or bell))) and		
		(@ad<=19991124 or @rlad<=19991124)) ((((first with		
		(film or coating or layer)) or ((silicon adj oxide) or SiO)) and		
		((second with (film or coating or layer)) or ((silicon adj		
		nitride) or SiN)) and ((clean\$3) near5 (tube or chamber or		
		wall or exhaust or bell)) and ((hydrogen adj fluoride) or HF))		
		and (@ad<=19991124 or @rlad<=19991124)) (exhaust		
		same (fluctuat\$3 with pressure)) (control\$3 same pressure same (exhaust adj pipe) same fluctuat\$3) (pressure same		
		(exhaust adj pipe) same fluctuat\$3) (pressure same		
	l	(cyliansi and hihe) same minimaras))	<u> </u>	

-	160	(((((exhaust adj pipe) same open same close) and (reactor	USPAT;	2004/06/18 17:46
		or chamber or tube)) and (etch\$3 or coat\$3 or deposit\$3 or	US-PGPUB;	
		clean\$3 or remov\$3)) not ((((((118/715,724,725) or	EPO; JPO;	
		(156/345.29) or (134/1,1.3) or (216/37,58,63) or	DERWENT;	
1		(438/694,699,703,706)).CCLS.) and ((first with (film or	IBM_TDB	
		coating or layer)) or ((silicon adj oxide) or SiO)) and		
		((second with (film or coating or layer)) or ((silicon adj		
		nitride) or SiN)) and ((clean\$3 or etch\$3) same ((hydrogen		
		adj fluoride) or HF))) and (@ad<=19991124 or		
1		@rlad<=19991124)) ((((((118/715,724,725) or		
İ		(156/345.29) or (134/1,1.3) or (216/37,58,63) or		
				ļ
		(438/694,699,703,706)).CCLS.) and ((first with (film or		
		coating or layer)) or ((silicon adj oxide) or SiO)) and		
İ		((second with (film or coating or layer)) or ((silicon adj		
-	1	nitride) or SiN)) and ((clean\$3 or etch\$3) same ((hydrogen		
		adj fluoride) or HF))) and (@ad<=19991124 or		1
		@rlad<=19991124)) not (((hydrogen adj fluoride) or HF)		
		with (dip or solution or wet))) ((((first with (film or coating		
	1	or layer)) or ((silicon adj oxide) or SiO)) and ((second with		
	1 -	(film or coating or layer)) or ((silicon adj nitride) or SiN))		
		and ((clean\$3 or etch\$3) same ((hydrogen adj fluoride) or	1	
		HF) same (tube or wall or exhaust or bell))) and		
		(@ad<=19991124 or @rlad<=19991124)) ((((first with		
		(film or coating or layer)) or ((silicon adj oxide) or SiO)) and		
1		((second with (film or coating or layer)) or ((silicon adj		
		nitride) or SiN)) and ((clean\$3) near5 (tube or chamber or		
		wall or exhaust or bell)) and ((hydrogen adj fluoride) or HF))	1	
		and (@ad<=19991124 or @rlad<=19991124)) (exhaust		
		same (fluctuat\$3 with pressure)) (control\$3 same pressure		
		same (exhaust adj pipe) same fluctuat\$3) (pressure same		
		(exhaust adj pipe) same fluctuat\$3))) not engine		
_	112		LICDAT.	2004/06/19 10:10
_	112	((((((exhaust adj pipe) same open same close) and (reactor	USPAT;	2004/06/18 19:19
		or chamber or tube)) and (etch\$3 or coat\$3 or deposit\$3 or	US-PGPUB;	
		clean\$3 or remov\$3)) not ((((((118/715,724,725) or	EPO; JPO;	
		(156/345.29) or (134/1,1.3) or (216/37,58,63) or	DERWENT;	
		(438/694,699,703,706)).CCLS.) and ((first with (film or	IBM_TDB	
		coating or layer)) or ((silicon adj oxide) or SiO)) and		
		((second with (film or coating or layer)) or ((silicon adj		
[nitride) or SiN)) and ((clean\$3 or etch\$3) same ((hydrogen		
		adj fluoride) or HF))) and (@ad<=19991124 or		
		@rlad<=19991124)) ((((((118/715,724,725) or		
		(156/345.29) or (134/1,1.3) or (216/37,58,63) or		
]		(438/694,699,703,706)).CCLS.) and ((first with (film or		
[coating or layer)) or ((silicon adj oxide) or SiO)) and		
		((second with (film or coating or layer)) or ((silicon adj		
		nitride) or SiN)) and ((clean\$3 or etch\$3) same ((hydrogen		
		adj fluoride) or HF))) and (@ad<=19991124 or		
		@rlad<=19991124)) not (((hydrogen adj fluoride) or HF)		
		with (dip or solution or wet))) ((((first with (film or coating		
		or layer)) or ((silicon adj oxide) or SiO)) and ((second with		
		(film or coating or layer)) or ((silicon adj nitride) or SiN))		
		and ((clean\$3 or etch\$3) same ((hydrogen adj fluoride) or		
		HF) same (tube or wall or exhaust or bell))) and		
		(@ad<=19991124 or @rlad<=19991124)) ((((first with		
		(film or coating or layer)) or ((silicon adj oxide) or SiO)) and		
ļ [((second with (film or coating or layer)) or ((silicon adj		
		nitride) or SiN)) and ((clean\$3) near5 (tube or chamber or		
		wall or exhaust or bell)) and ((hydrogen adj fluoride) or HF))		
		and (@ad<=19991124 or @rlad<=19991124)) (exhaust		
]	same (fluctuat\$3 with pressure)) (control\$3 same pressure		
		same (exhaust adj pipe) same fluctuat\$3) (pressure same	İ	
		(exhaust adj pipe) same fluctuat\$3))) not engine) and		
		(@ad<=19991124 or @rlad<=19991124)		
		8:27:08 DM Dage 8		

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